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Specification Amendments

Please replace paragraph 0030 with the following replacement paragraph:

[0030] Referring to Figure 2, an illustrative embodiment of a wastewater treatment system of the present invention is generally indicated by reference numeral 40. The system 40 includes a CMP wastewater collection tank 42 which typically receives raw or untreated CMP wastewater 43 from a CMP apparatus 41A ~~(not shown)~~. In a separate treatment process, the CMP wastewater collection tank ~~43~~ 42 may receive raw Cu-CMP wastewater 45 produced during a Cu-CMP process from Cu-CMP apparatus 41B. An outlet 42a extends from the CMP wastewater collection tank 42, and one or a pair of pumps 44 is provided in the outlet 42a. A holding tank 54 is provided in fluid communication with the outlet of the pump or pumps 44.

Please replace paragraph 0031 with the following replacement paragraph:

[0031] In a semiconductor fabrication process, prior to the

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dicing and packaging of the individual integrated circuit chips formed on the front side of a wafer (not shown), the wafer is typically ground on the backside to remove unwanted bulk semiconductor material. Accordingly, a BG (backside grind) wastewater collection tank 46, which receives BG wastewater 47 produced during a wafer backgrind process from wafer backgrind apparatus 41A, for example, is typically provided in fluid communication with the holding tank 54 through one or a pair of pumps 48 that are provided in an outlet 46a extending from the BG wastewater collection tank 46.

Please replace paragraph 0032 with the following replacement paragraph:

[0032] An outlet 54a extends from the holding tank 54, and one or a pair of pumps 56 is provided in the outlet 54a. The pump or pumps 56 are provided in fluid communication with a reaction tank 58. A backwash wastewater collection tank 50 receives BW (backwash) wastewater 51, typically produced during semiconductor wafer rinsing processes, for example, from wafer rinsing apparatus 41D. An outlet 50a extends from the backwash wastewater collection tank 50, and one or a pair of pumps 52 is provided in the outlet 50a. The pump or pumps 52 are provided in

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fluid communication with the reaction tank 58.